FORM PTO-1449				Docket Number (Optional) 81716.0122		Application Number 10/810,309				
O PINFORMATION DISCLOSURE CITATION IN AN APPLICATION				Applicant AKASAKI, et al.						
JUL 0 2 2004 (Use several sheets if necessary)				Filing Date , March 26, 2004		Group Art Unit 2811				
U.S. PATENT DOCUMENTS										
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME		CLASS	SUBCLASS	FILING DATE IF APPROPRIATE			
72	5,122,845 (counterpart Japanese App. 2-229476)	06/16/92	MANABE, et al.							
7	4,855,249 (counterpart Japanese App. 62-119196)	08/08/89	AKASAKI, et al.				·			
72	6,566,218 (counterpart Japanese App. 2002-043223)	.05/20/03	ОТА	NI, et al.						
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FOREIGN PATENT DOCUMENTS										
ΞX	DOCUMENT NUMBER	DATE		COUNTRY	CLASS	SUBCLASS	Transla	ation NO		
172	4-321280	11/11/92		JAPAN			Abstract			
TL	62-119196 (counterpart U.S. Patent 4,855,249)	05/30/87		JAPAN			Abstract			
TL	2-229476 (counterpart U.S. Patent 5,122,845)	09/12/90		JAPAN			Abstract			
TL	2002-043223 (counterpart U.S. Patent 2002-043223)	02/08/02		JAPAN			Abstract			
	OTHER DOCUMENT	S (including A	Autho	r, Title, Date, Per	tinent Pages,	Etc.)				
	SUDA, et al., "Heteroepitaxial Growth of Group-III Nitrides on Lattice-Matched Metal Boride ZrB ₂ (0001) by Molecular Beam Epitaxy – Department of Electronic Science and Engineering, Kyoto University – 13 th International Conference Crystal Growth, August, 2001, 02a-SB2-20									
TL	YUKAWA, et al. – 62 nd Autumn Meeting, 2001; Japan Society of Applied Physics, 12-R-14									
R	Yohei YUKAWA, "Study on the crystal growth and properties of group-III nitride semiconductors on ZrB₂ substrates by metalorganic vapor phase epitaxy" Department of Electronic Science and Engineering Graduate School of Meijo University									
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EXAMINER	DATE CONSIDERED	07/20/05	

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.